

Library



Bharatiya Vidya Bhavan's

# Sardar Patel College of Engineering



(A Government Aided Autonomous Institute)  
Munshi Nagar, Andheri (West), Mumbai – 400058.

**End Sem Re - Exam**

June 2017

Q. P. Code:  
Max. Marks: 100  
Duration: 3 hr  
Class: **Third Year**  
Program: **Electrical Engineering**  
Name of the Course: **Elective – VLSI**  
Course Code : BTE332

Semester: VI  
**MASTER FILE**

**Instructions:**

- Question One is Compulsory.
- Solve any four of remaining six questions.
- Illustrate your answers with neat sketches wherever necessary.
- Assume suitable data if required.
- Preferably, write the answers in sequential order.

Question No.	Module Number	Course Outcome	Max. Marks
Q1.			
A) Compare the two technology scaling methods, namely, (i) the constant electric-field scaling and (ii) the constant power-supply voltage scaling. In particular, show analytically by using equations how the delay time, power dissipation, and power density are affected in terms of the scaling factor, S.	1	1	5
B) Compare BJT, NMOS and CMOS technology.	1	1	5
C) Explain simplified process sequence for the fabrication of the n-well CMOS integrated circuit with a single	1	1	5

polysilicon layer, showing only major fabrication steps.

D) Consider a simple abrupt pn-junction, which is reverse-biased with a voltage  $V_{bias}$ . The doping density of the n-type region is  $N_D = 10^{19} \text{ cm}^{-3}$ , and the doping density of the p-type region is given as  $N_A = 10^{16} \text{ cm}^{-3}$ . The junction area is  $A = 20 \mu\text{m} \times 20 \mu\text{m}$ .

- I) Find built in junction capacitance.  
 II) Calculate the Zero bias junction capacitance.

Given:

$$\epsilon_0 = 8.85 \times 10^{-14} \text{ F/cm}, \epsilon_{si} = 11.7 * \epsilon_0$$

$$q = 1.6 \times 10^{-19} \text{ C}, k = 1.3 \times 10^{-23} \text{ J/K}$$

Intrinsic carrier concentration of silicon (Si)  $n_i = 1.45 \times 10^{10} \text{ (cm}^{-3}\text{)}$  at 300K.

$$\text{Thermal voltage } kT/q = 0.026 \text{ V.}$$

Q2.

A) Give the CMOS inverter voltage transfer characteristics and operating regions. 2 2 5

B) Design a resistive-load inverter with  $R = 1 \text{ k}\Omega$ , such that  $V_{OL} = 0.6 \text{ V}$ . The nMOS driver transistor has the following parameters:

$$V_{DD} = 5.0 \text{ V}$$

$$V_{T0} = 1 \text{ V}$$

$$\gamma = 0.2 \text{ V}^{1/2}$$

$$\lambda = 0$$

$$\mu_n C_{ox} = 22.0 \mu\text{A/V}^2$$

(a) Determine the required aspect ratio,  $W/L$ .

(b) Determine  $V_{IL}$  and  $V_{IH}$ .

(c) Determine noise margins  $N_{ML}$  and  $N_{MH}$ .

C) Consider a CMOS inverter circuit with the following parameters: 2 2 10

$$V_{DD} = 5\text{V}$$

$$V_{T0,n} = 0.6 \text{ V}$$

$$V_{T0,p} = -0.7 \text{ V}$$

$$k_n = 100 \mu\text{A/V}^2$$

$$k_p = 40 \mu\text{A/V}^2$$

Calculate the noise margins of the circuit. Notice that the CMOS inverter being considered here has  $k_R = 2.5$  and  $V_{T0,n} \neq |V_{T0,p}|$  hence, it is not a symmetric inverter.

Q.3				
A)	Draw the circuit and layout of CMOS NAND2 gate.	2	2	5
B)	Define: i) Pseudo-nMOS gate, ii) transmission gate. Implement two input multiplexer using CMOS transmission gate.	3	3	5
C)	Write short note on SR latch circuit.	3	3	5
D)	Write short note pass transistor logic..	3	3	5
Q.4				
A)	Give the classification of semiconductor memories. Draw typical random access memory array organization.	4	3	5
B)	Design a 4-bit X 4-bit NOR based ROM array to store following data stream. Also write its column and rows combination. Data: 1001 1110 0110 1001 Draw layout for circuit designed.	4	3	10
C)	Discuss the operation of resistive-load SRAM Cell.	4	3	5
Q.5				
A)	Discuss the operation of three transistor DRAM Cell.	4	3	10
B)	Explain Partial-product generation.	5	3	5
C)	Write short note on barrel shifter.	5	3	5
Q.6				
A)	What is clock skew? What are the sources of clock skew? How it can be overcome?	6	4	5
B)	Explain clock system architecture.	6	4	5
C)	Explain in detail global clock generator of clock system.	6	4	5
D)	Comment on the advantages and disadvantages of H-trees and clock grids. How does the hybrid tree/grid improve on a standard grid?	6	4	5
Q.7				
A)	Explain how an electrostatic discharge event could cause latchup on a CMOS chip	7	4	5
B)	Define: A) VDD & GND pads. B) Input and Output Pads. C) Bidirectional pads.	7	4	5

- D) Analog pads.  
Draw bidirectional pad circuitry.
- |    |   |   |   |   |
|----|---|---|---|---|
| C) | Write short note on Elmore delay.   | 7 | 4 | 5 |
| D) | Define crosstalk. What are the effect of crosstalk delay and crosstalk noise on interconnect. | 7 | 4 | 5 |